

Preface

Citation for published version (APA):

Elam, J. W., De Gendt, S., Londergan, A., Bent, S. F., van der Straten, O., Delabie, A., & Roozeboom, F. (2011). Preface: Atomic Layer Deposition Applications 7. *ECS Transactions*, 41(2), III-IV.

Document status and date:

Published: 01/01/2011

Document Version:

Publisher's PDF, also known as Version of Record (includes final page, issue and volume numbers)

Please check the document version of this publication:

- A submitted manuscript is the version of the article upon submission and before peer-review. There can be important differences between the submitted version and the official published version of record. People interested in the research are advised to contact the author for the final version of the publication, or visit the DOI to the publisher's website.
- The final author version and the galley proof are versions of the publication after peer review.
- The final published version features the final layout of the paper including the volume, issue and page numbers.

[Link to publication](#)

General rights

Copyright and moral rights for the publications made accessible in the public portal are retained by the authors and/or other copyright owners and it is a condition of accessing publications that users recognise and abide by the legal requirements associated with these rights.

- Users may download and print one copy of any publication from the public portal for the purpose of private study or research.
- You may not further distribute the material or use it for any profit-making activity or commercial gain
- You may freely distribute the URL identifying the publication in the public portal.

If the publication is distributed under the terms of Article 25fa of the Dutch Copyright Act, indicated by the "Taverne" license above, please follow below link for the End User Agreement:

www.tue.nl/taverne

Take down policy

If you believe that this document breaches copyright please contact us at:

openaccess@tue.nl

providing details and we will investigate your claim.

PREFACE

The seventh symposium on Atomic Layer Deposition Applications was held October 10 through 12, 2011 in Boston, Massachusetts, as part of the 220th Meeting of the Electrochemical Society.

The focus of this symposium is the continuously expanding realm of Atomic Layer Deposition (ALD) applications. ALD allows the precise deposition of ultra-thin, highly conformal coatings over complex, 3D topographies with controlled composition and properties. In its 7th successful year, this symposium has become a forum for sharing cutting edge research in the various technologies where ALD is currently used. Emerging and non-mainstream ALD applications are also of special interest.

This issue of the *ECS Transactions* contains 36 peer reviewed papers presented at the symposium. The papers are organized into Chapters generally following the order and structure of the symposium sessions. Featured ALD topics include ALD for photovoltaics, ALD for batteries and fuel cells, dielectrics for state-of-the-art transistors and capacitors, and the ALD of metals and metal nitrides. A number of papers report on advances in ALD precursor and equipment development, and in particular the continued progress in high throughput ALD equipment.

We wish to thank the invited speakers for their outstanding contributions: Ivo Raaijmakers, *ASM International*, Soo-Hyun Kim, *Yeungnam University*, Johan Swerts, *IMEC*, Kornelius Nielsch, *University of Hamburg*, Fritz Prinz, *Stanford University*, Titta Aaltonen, *University of Oslo*, Jane Chang, *University of California*, Simon Elliott, *Tyndall National Institute*, Christian Wenger, *IHP*, Jacques Kools, *Encapsulix SAS*, Thomas Proslie, *Argonne National Laboratory*, Byunghoon Yoon, *University of Colorado*, Gijs Dingemans, *Technische Universiteit Eindhoven*, Nicolas Tetreault, *Ecole Polytechnique Federale de Lausanne*

The financial support of the symposium sponsors is gratefully acknowledged: Air Liquide, Applied Materials, Cambridge NanoTech, Gelest and Tokyo Electron.

Jeffrey W. Elam
Fred Roozeboom
Annelies Delabie
Oscar van der Straten
Stacey F. Bent
Stefan De Gendt
Ana Londergan

